TELIC

Photomask Blanks Standard- Standard Optical Lithography

Substrates

- Soda Lime
- Borosilicate (Eagle, D263, AF32, Borofloat)
- White Crown (B-270, BK-7)
- Quartz (Synthetic Fused Silica)

Applications

- Reticles, Master Grade
- Print & Test Grade

SUBSTRATE SPECIFCATIONS

SIZES: Thickness Squares 2" through 7"

THICKNESS: 0.010" - 0.220" (0.50mm - 6mm) non standard thickness is available upon request

SURFACE: All plates are polished on both sides and inspected to be free of glass defects > 2 microns

FLATNESS: ≤15 microns

FILM SPECIFICATIONS

CHROME: Vacuum Deposited, DC Sputtered in Class 100 Environment

THICKNESS/OPTICAL DENSITY: Standard: 1100Å ± 10% / O.D. = 2.8 ± 0.2 @ 530mm. Custom thicknesses up to 5 microns

REFLECTIVITY:

Low Reflective - LRC	8% @ 450nm
Mid Reflective - MRC	<33% @ 450nm
High Reflective - HRC	>48% @ 450nm
Blue - R632	<5% @ 632nm
Blue/Chrome/Blue - R632/632	<5% @ 632nm Both Sides
Green - R850	<5% @ 850nm
Green/Chrome/Green - R850/850	<5% @ 850nm Both Sides

PROCESS:

- Etchable in all conventional Wet Etch systems
- Plasma Grade recommended for Dry Etch systems

PHOTORESIST:

5300Å AZ 1500 filtered to 0.045 microns at point of use. Fringless and Regular Spin Available. Custom Photoresist options include all widely used positive and negative optical. Including: AZ MIR701, AZ P4600, AZ 5206, AZ 9260, AZ nLOF 2000, AZ 6615, AZ ECI3027 S1800, HR200, IP3500, IP3600, PMMA, AR N7700, LOR A, LOR B, PMGI